

directional deposition process on a planar substrate. In fact, in the case of Wernberg et al., the deposition process involves tilting the substrate toward the incoming vapor, and thus does not use a substantially static substrate deposition geometry. Therefore, for all of these reasons, claim 1 is patentably distinguishable from the combination of the AASA and Vijayakumar et al. or Wernberg et al.

Claims 2-11 are also patentably distinguishable from the combination of the AASA and Vijayakumar et al. or Wernberg et al. by virtue of their dependence from claim 1, as well as their additional recitations. New claim 16 is patentably distinguishable from the combination of the AASA and Vijayakumar et al. or Wernberg et al. for at least the same reasons as claim 1.

Applicants respectfully submit that the application is in condition for allowance and request reconsideration. Should there be any questions or concerns regarding this application, the Examiner is invited to contact Applicants' undersigned representative by telephone.

Respectfully submitted,

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